

## Electronic Supplementary Information

# Multifunctional Mg<sub>2</sub>Si monolayer with negative Poisson's ratio and ultrahigh thermoelectric performance at room temperature

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**Computational Methods** During the process of searching the ground state of Mg<sub>2</sub>Si monolayer by CALYPSO package, we consider the stoichiometric of 2:1. The initial structures are randomly generated through plane group symmetry operations and then relaxed. We select 60% of the low-energy structures to produce next generation. Finally, after 30 generations, over 1500 planar and folded Mg<sub>2</sub>Si monolayer structures are obtained. We select and optimize the top 10 low-energy structures to find the true ground state structure. It is found that the Mg<sub>2</sub>Si monolayer proposed in this work is the most stable by stability calculation.

The in-plane Young's modulus ( $E(\theta)$ ) and Poisson's ratio ( $\nu(\theta)$ ) with directional dependence can be calculated based on the theory of elastic solids,<sup>1</sup> as follows:

$$E(\theta) = \frac{C_{11}C_{22} - C_{12}^2}{C_{11} \sin^4 \theta + C_{22} \cos^4 \theta + A \sin^2 \theta \cos^2 \theta} \quad (1)$$

$$\nu(\theta) = -\frac{B \sin^2 \theta \cos^2 \theta - C_{12}(\sin^4 \theta \cos^4 \theta)}{C_{11} \sin^4 \theta + C_{22} \cos^4 \theta + A \sin^2 \theta \cos^2 \theta} \quad (2)$$

where  $C_{ij}$  is the elastic constant,  $\theta$  is the angle,  $A = (C_{11}C_{22} - C_{12}^2)/C_{66} - 2C_{12}$  and  $B = C_{11} + C_{22} - (C_{11}C_{22} - C_{12}^2)/C_{66}$ .

The cohesive energy of Mg<sub>2</sub>Si monolayer can be calculated by the following equation:

$$E_{coh} = \frac{mE_{Mg} + nE_{Si} - E_{Mg_2Si}}{m + n} \quad (3)$$

where  $E_{Mg}$  and  $E_{Si}$  are the energies of the Mg atom and the Si atom, respectively.  $E_{Mg_2Si}$  is the total energy of the Mg<sub>2</sub>Si monolayer. The  $m$  and  $n$  represent the number of Mg and Si atoms in the primary cell, respectively.

The lattice thermal conductivity of Mg<sub>2</sub>Si monolayer using Cahill–Watson–Pohl (CWP) model ( $\kappa_{cwp}$ ) is calculated by the following equation:<sup>2</sup>

$$\kappa_{cwp} = \left(\frac{\pi}{6}\right)^{1/3} k_B n^{2/3} \sum_i v_i \left(\frac{T}{\theta_i}\right)^2 \int_0^{\theta_i/T} \frac{x^3 e^x}{(e^x - 1)^2} dx \quad (4)$$

where  $k_B$ ,  $n$ ,  $v_i$ , and  $\theta_i$  are Boltzmann constant, atom density, the phonon velocity and Debye

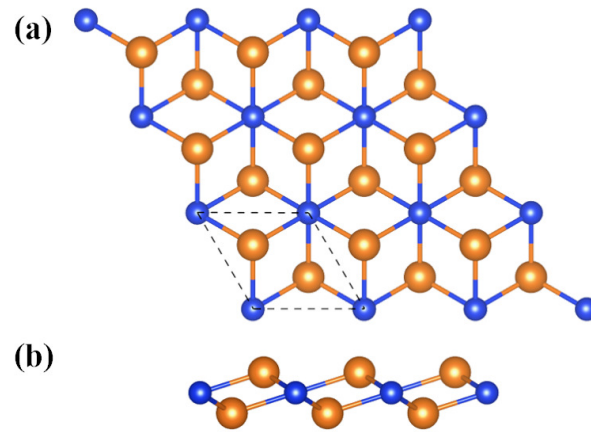
temperature of the acoustic branch  $i$ , respectively. The Debye temperature is  $\theta_i = v_i(\frac{\hbar}{k_B})(6\pi^2n)^{1/3}$ .

The carrier mobility of 2D materials can be calculated by<sup>3</sup>

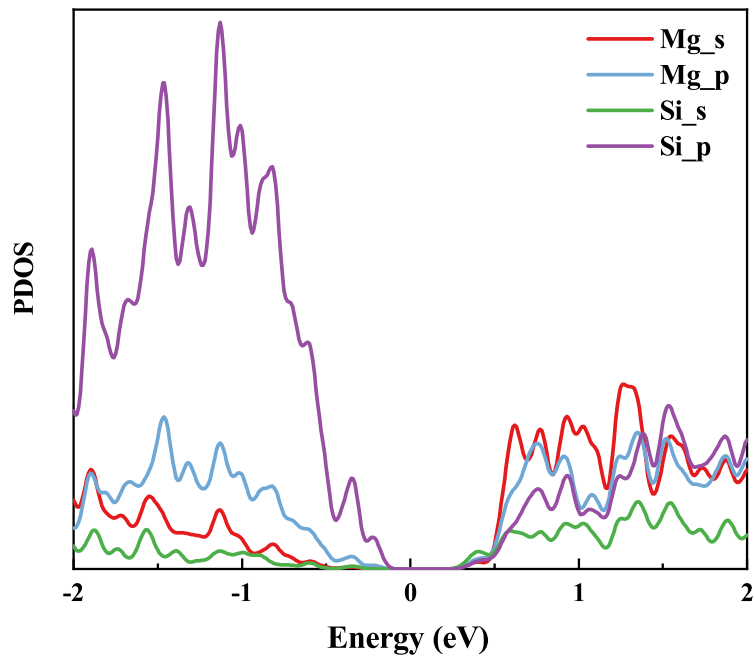
$$\mu_{2D} = \frac{e\hbar^3 C_{2D}}{k_B T m^* m_d^* E_1^2} \quad (5)$$

where  $e$ ,  $C_{2D}$ ,  $k_B$ ,  $m^*$ ,  $m_d^*$ ,  $E_1$  are electron charge, elastic constant, Boltzmann constant, effective mass, average effective mass and deformation potential constant, respectively. The  $C_{2D}$  can be calculated by  $C_{2D} = [\partial^2 E / \partial(\Delta a / a_0)^2] / S_0$ , where  $E$ ,  $a_0$ ,  $\Delta a$ , and  $S_0$  are the total energy of the system under strain, lattice parameters, the change value of lattice parameters, and the area of unstrained unit cell after structure optimization, respectively.  $m^*$  can be obtained from  $m^* = \hbar^2 / (\partial^2 E / \partial k^2)$ , and  $m_d^* = \sqrt{m_x^* m_y^*}$ . The  $E_1$  can be obtained by  $E_1 = \partial E_{edge} / \partial E(\Delta a / a_0)$ , where  $E_{edge}$  is the band-edge energy of Mg<sub>2</sub>Si monolayer. Therefore, we can get the  $\tau$  from carrier mobility as follows

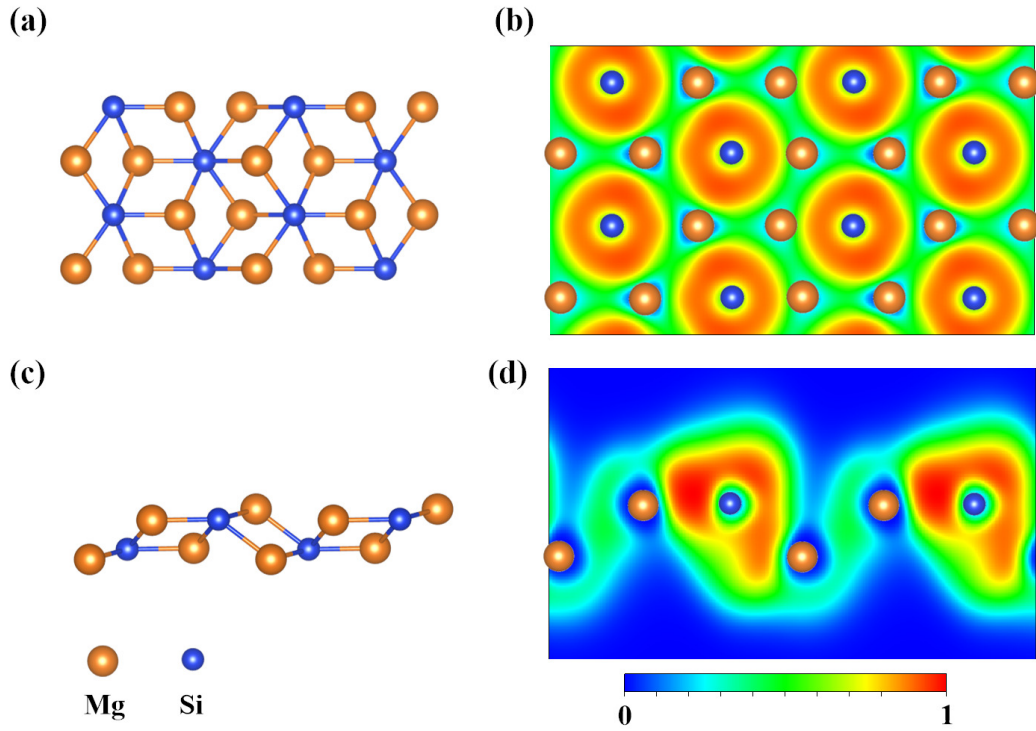
$$\tau = \frac{\mu m^*}{e} \quad (6)$$



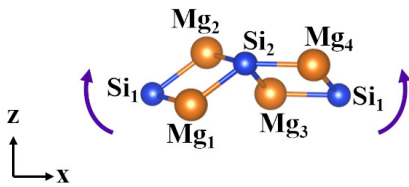
**Fig. S1** The (a) top and (b) side views of T-phase  $\text{Mg}_2\text{Si}$  monolayer crystal structure. The blue balls represent Si atoms and the orange balls represent Mg atoms.



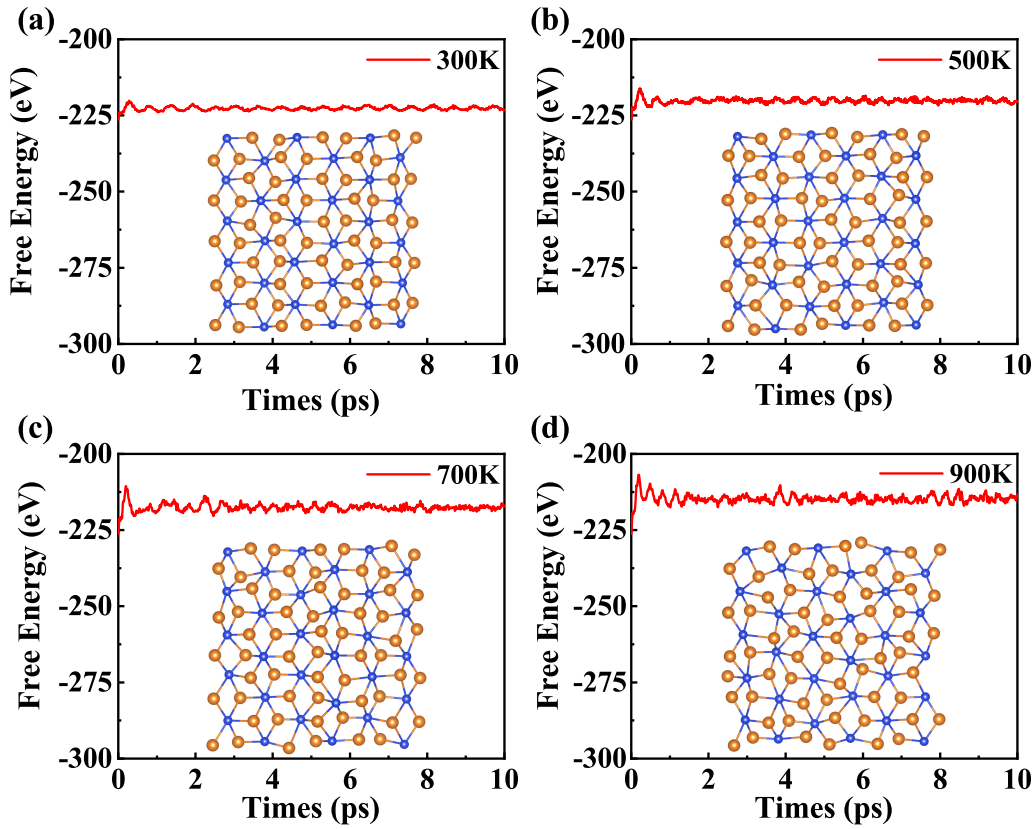
**Fig. S2** Projected density of states of  $\text{Mg}_2\text{Si}$  monolayer.



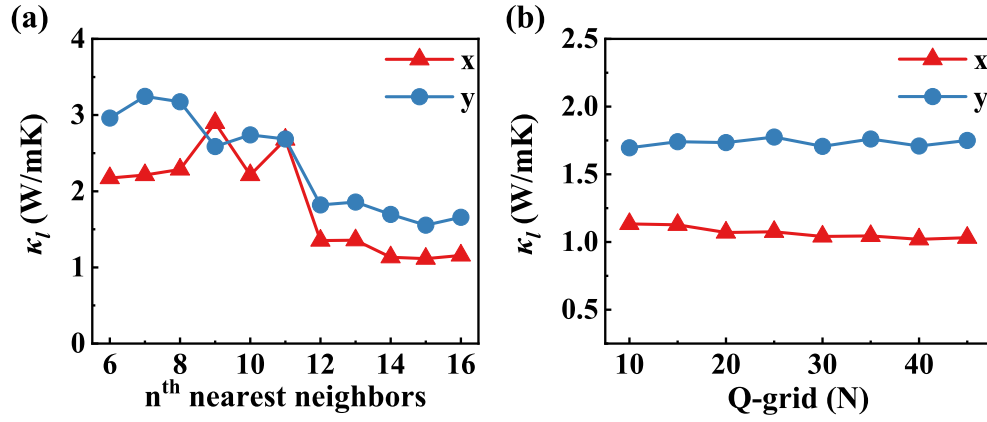
**Fig. S3** (a) Top and (c) side views of two-dimensional  $\text{Mg}_2\text{Si}$ . Electronic localization function of (b) top and (d) side views of  $\text{Mg}_2\text{Si}$  monolayer.



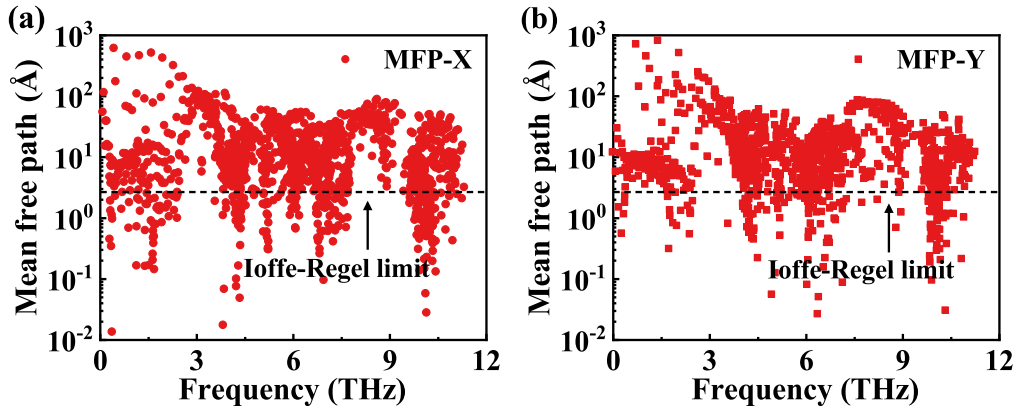
**Fig. S4** Variation of  $\text{Mg}_2\text{Si}$  monolayer structure under stretch strain along  $x$  direction.



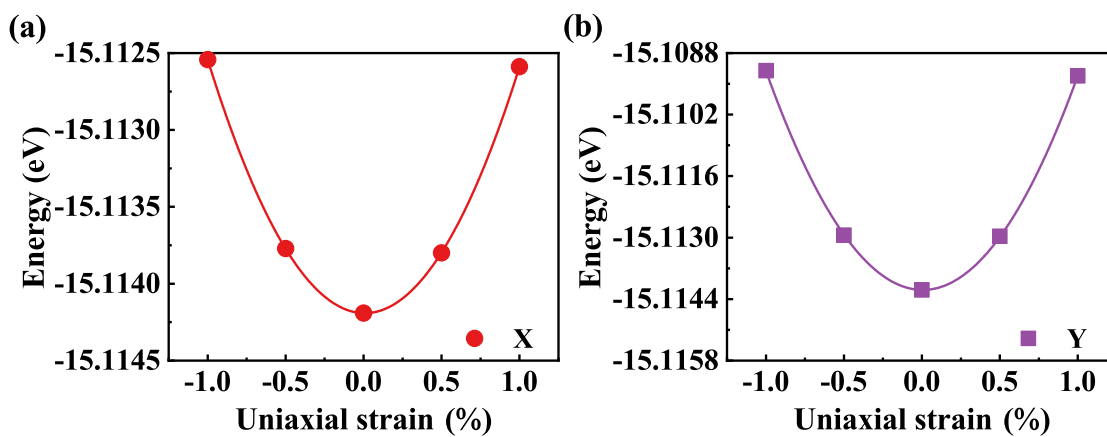
**Fig. S5** The fluctuation of free energy of two-dimensional Mg<sub>2</sub>Si monolayer (a-d) at 300-900 K is achieved by AIMD simulations lasting 10 ps. The inset of figures show the crystal structures of Mg<sub>2</sub>Si monolayer at different temperatures. The curves of free energy at different temperatures do not fluctuate widely after 1 ps, providing sufficient evidence for its thermal stability. More computational resources will be required when the longer simulation time is used. The simulation time of 10 ps not only ensures the accuracy of calculation, but also considers the utilization of computational resources. And in many other two-dimensional materials,<sup>4,5</sup> the thermal stability of the materials are also calculated by using molecular dynamis simulations lasting 10 ps. Therefore, simulation time of 10 ps is enough to determine the thermal stability of Mg<sub>2</sub>Si monolayer.



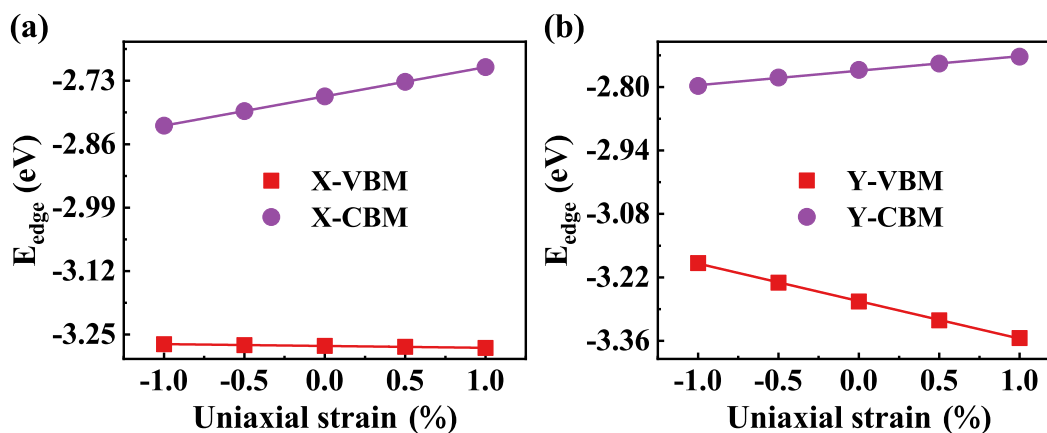
**Fig. S6** Convergence test of the lattice thermal conductivity of  $\text{Mg}_2\text{Si}$  monolayer with the change of (a) nearest neighbors and (b) Q-grid.



**Fig. S7** The (a, b) phonon mean free path of  $\text{Mg}_2\text{Si}$  monolayer as functions of the frequency at 300 K.

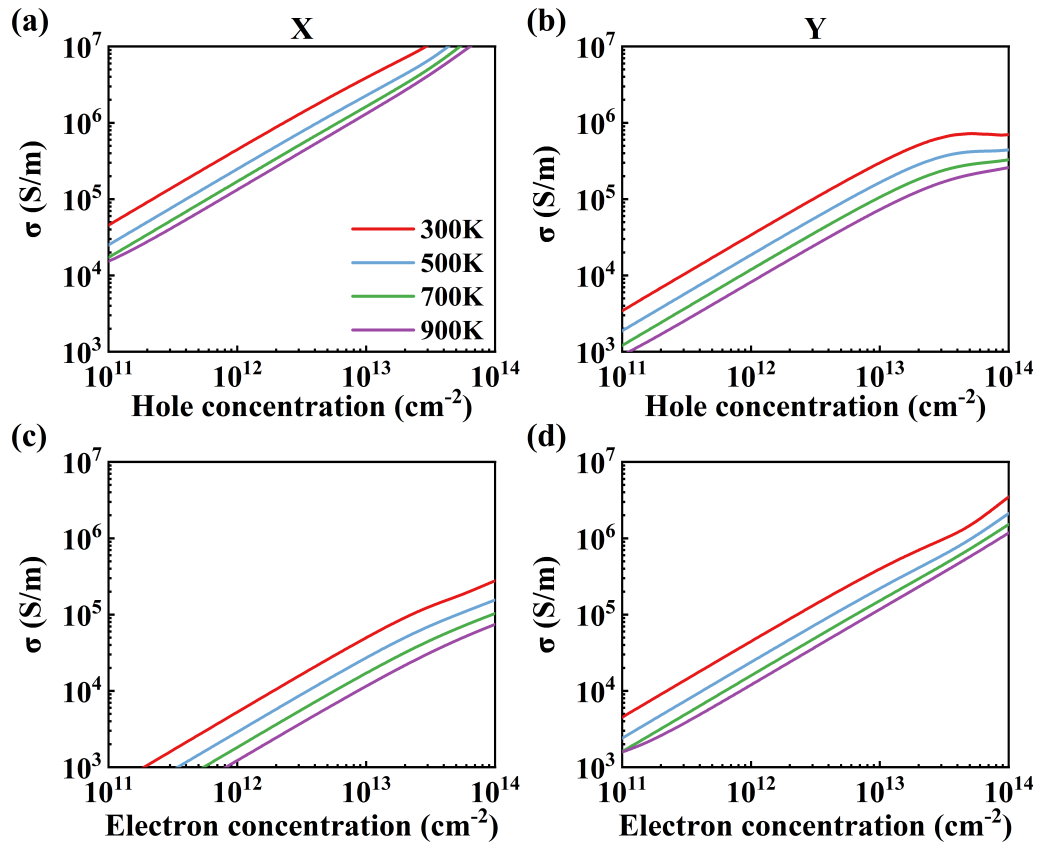


**Fig. S8** The total energy of Mg<sub>2</sub>Si monolayer under different strain with respect to the strain along (a) x and (b) y directions.

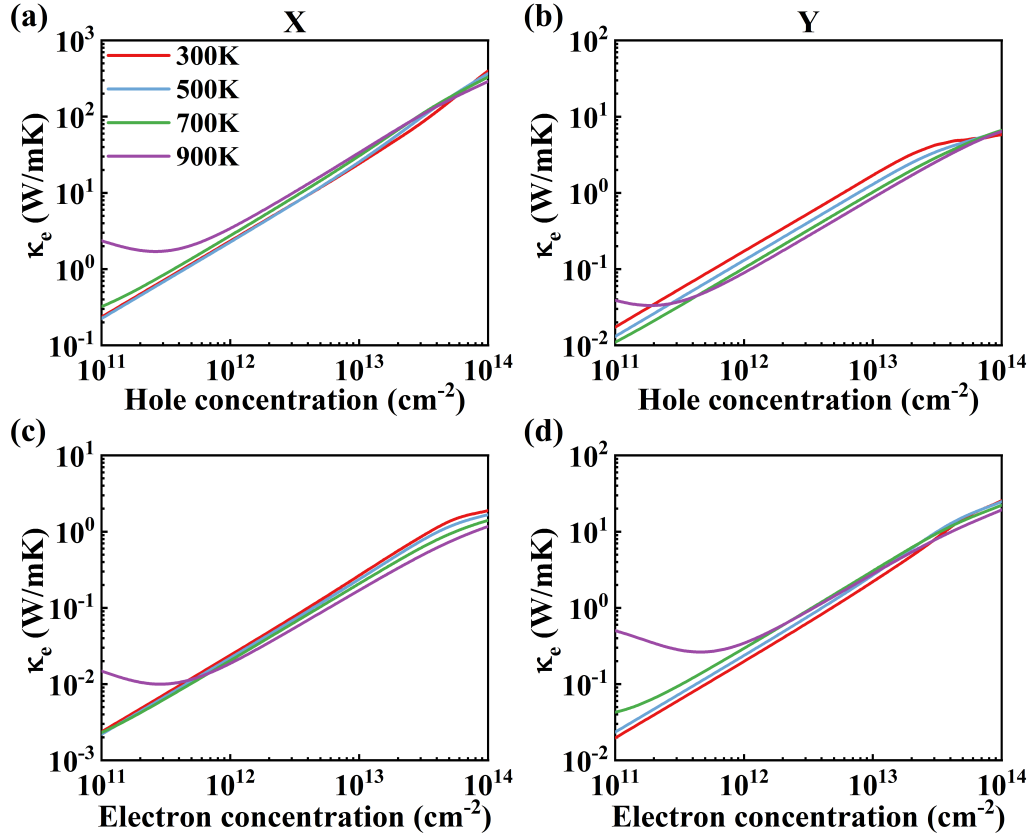


**Fig. S9** The edge energies shift of VBM and CBM of Mg<sub>2</sub>Si monolayer with respect to the strain along (a) x and (b) y directions.





**Fig. S10** The electrical conductivity of the  $\text{Mg}_2\text{Si}$  monolayer as the function of (a, b) hole or (c, d) electron doping concentration along  $x$  or  $y$  direction at different temperatures at HSE06 method.



**Fig. S11** The electronic thermal conductivity of the  $\text{Mg}_2\text{Si}$  monolayer as the function of (a, b) hole or (c, d) electron doping concentration along  $x$  or  $y$  direction at different temperatures at HSE06 method.

**Table S1** Calculated equilibrium lattice parameters ( $a$  and  $b$  in Å), buckling distance ( $d$  in Å), bond length (Mg-Si in Å) and band gap ( $E_g$  in eV) of the 2D Mg<sub>2</sub>Si monolayer.

Mg <sub>2</sub> Si	$a$	$b$	$d$	<Mg-Si>1	<Mg-Si>2	<Mg-Si>3	<Mg-Si>4	$E_g$
our	7.319	4.363	2.036	2.672	2.690	2.670	2.681	0.51 (PBE) 0.94 (HSE06)
other <sup>6</sup>	7.28	4.34	2.03					0.95 (HSE06)

**Table S2** Calculated the elastic coefficient ( $C_{2D}$  in J/m<sup>2</sup>), DP constant ( $E_1$  in eV), effective mass ( $m^*$  in  $m_0$ ), carrier mobility ( $\mu$  in cm<sup>2</sup>/Vs) and relaxation time ( $\tau$  in fs) of 2D Mg<sub>2</sub>Si at room temperature.

direction	carrier type	$C_{2D}$	$E_1$	$m^*$	$\mu$	$\tau$
$x$	electron	16.29	6.00	0.38	76.15	16.39
	hole	16.29	-0.38	0.59	15720.23	5298.82
$y$	electron	49.42	3.20	0.30	1029.36	174.65
	hole	49.42	-8.28	0.11	525.63	33.82

**Table S3** Calculated Poisson's ratio and ZT of Mg<sub>2</sub>Si monolayer and comparison materials. The ZT values represent their maximum at 300 K.

2D material	Poisson's ratio	ZT
Mg <sub>2</sub> Si (this work)	-0.364	2.51
C <sub>2</sub> H <sup>7</sup>	-0.071	0.93
C <sub>2</sub> F <sup>7</sup>	-0.042	0.80
Ag <sub>2</sub> S <sup>8</sup>	-0.11	0.72
AgCuS <sup>8</sup>	-0.06	0.84
pentagonal tellurene <sup>9</sup>	-0.01	2.84
Si <sub>9</sub> C <sub>15</sub> <sup>10</sup>	-0.175	1.25 (800 K)

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